

Probe Information

Typically, the linear array 4 point probe are specified by the following parameters:

Pin material	Typically Tungsten Carbide
Pin spacing	Typically 1 mm; others available: 20 mil, 25 mil, 40 mil, 63mil, etc(1 mil =0.001 inch = 25.4 um)
Pin tip radius	Typically Radii : 40um, 100um, 200um, 500um, etc.
Pin compression force	Typically 100 gm to 200 gm

For most of the probes used, the only really important distinction is the tip radius, which affects the penetration or contact pressure. The most commonly used probes are given names as type A, B, C, etc. The following is a summary of the most popular probe types:

(1 mil =0.001 inch = 25.4 um)

<i>Type</i>	<i>Tip R</i>	<i>Force</i>	<i>Spacing</i>	<i>KLA Part No.</i>	<i>Typical Application</i>
A	40u(1.6mil)	100g	1 mm(40mil)	50-0002-01	Metal Film
B	100u(4mil)	100g	1 mm(40mil)	50-0002-02	General Metal, Hi dose implant
C	200u(8mil)	100g	1 mm(40mil)	50-0002-03	Medium dose implant [Rs = 1000ohm/sq]
D	500u(20mil)	70g	1 mm(40mil)	50-0002-05	Low Dose implant. Very thin metal film such as TiN, ti, etc.
E	40u(1.6mil)	200g	.58mm(62.5mil)	50-0002-06	Thick substrate :dosed silicon wafers, diffusion
F	40u(1.6mil)	100g	.635 mm(25mil)	50-0002-10	Similiar to A probe for smaller [2mm]edge exclusion ,higher resolution measurement
G	100u(4mil)	100g	.635 mm(25mil)	50-0002-10	Similiar to B probe for smaller [2mm]edge exclusion ,higher resolution measurement
H	200u(8mil)	100g	.635 mm(25mil)	50-0002-11	Similiar to C probe for smaller [2mm]edge exclusion ,higher resolution measurement